



# Development of highly conductive and transparent copper doped zinc oxide thin films via 2-methoxyethanol modified sol–gel dip-coating technique

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## Abstract

Nanocrystalline copper doped zinc oxide thin films were prepared via a modified 2-methoxyethanol sol–gel dip-coating technique at various concentrations of copper in the range 0–5 wt%. The X-ray diffraction analysis confirmed the copper doped zinc oxide hexagonal wurtzite structure. The copper ions interstitially substitute zinc ions in the hexagonal structure which resulted in the decrease of the crystallite size from 25 nm to 16 nm. A decrease in the lattice parameters was observed up to 2 wt% of copper ions followed by an increase. Scanning electron microscopy showed a homogenous distribution of the prepared films along the glass substrates. Energy dispersive spectroscopy confirmed the stoichiometry and high purity of the prepared films. The optimum optical band gap was achieved at 2 wt% of the copper ion concentration. The prepared films showed a high transparency in the visible region with an average value of 89%. The *I*–*V* characteristics showed Ohmic behavior up to 3 V. The electrical resistivity showed a lowest value (0.2 Ω cm) for the film doped with 2 wt% of copper.

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## 1. Introduction

Transparent conducting thin films received a great deal of attention because they allow one to achieve large values of electrical conductivity, whilst maintaining high transmission in the visible range of the electromagnetic spectrum [1,2]. Since the advance of this type of materials, vast research and development have gone into commercialization of these thin film coatings [3,4]. The current commercial products are based on n-doped metal oxide thin films, so-called transparent conducting oxides (TCO's). Most of these transparent metal oxides are n-type semiconductors and are employed in various technological applications, such as heat-mirror window-coatings, which control the transmission of infrared energy into and out of buildings, photovoltaic cells, touch-screen technology, and light emitting and plasma screen displays [5–8].

However, p-type transparent metal oxides are nearly non-existent due to difficult fabrication and hole injection into metal oxide semiconductor materials [9,10]. Tin doped indium oxide (ITO) is one of the popular transparent metal oxides that has been widely investigated and used commercially [11]. ITO has electrical conductivity of  $\sim 10^4 \Omega^{-1} \text{cm}^{-1}$  and transmission of > 80%. This is close to metallic conductivity, in a material that is transparent, thus it has resulted in many important applications such as current spreading layers in light emitting diodes and thermal insulation for windows [12,13]. The high cost of indium and tin, however, has spawned the search for an alternative to ITO and zinc oxide is fast emerging as such.

The unique optoelectronic properties of zinc oxide, the low cost and its nontoxicity have attracted attention in the recent years [14–16]. The electrical and optical properties, high mechanical and chemical stability make zinc oxide the promising material for TCO's. The abundance of ZnO in nature makes it a lower cost material than the majority of the

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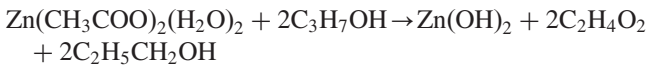
currently used TCO's (SnO<sub>2</sub>, ITO). The average amount of zinc available in earth's crust is 132 ppm while for indium, it is only 0.1 ppm and for tin, it is 40 ppm [17].

Herein, we developed a novel procedure to prepare copper doped zinc oxide thin films at different copper concentrations via a modified 2-methoxyethanol sol–gel dip-coating technique to improve the transparency and the conductivity of these films to be close to the ITO values.

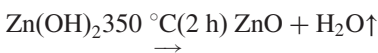
## 2. Experimental

In a typical synthesis, 1 mmol (0.22 g) of zinc acetate Zn(CH<sub>3</sub>COO)<sub>2</sub> × 2H<sub>2</sub>O was dissolved in 40 mL of 2-propanol to form a clear acetate solution. Then 1 mmol (0.076 g) of 2-methoxyethanol was added to the zinc acetate solution and kept stirring for 30 min at 60 °C until forming a homogeneous viscous solution. Glass substrates were cleaned by acetone in ultrasonic bath for 2 h, followed by washing with de-ionized water and then dried by nitrogen. The pre-cleaned quartz substrate was immersed into the viscous gel by dipping at cross-head speed 1 mm/min, left in the gel for 5 min and then withdrawn with the same cross-head speed. This process was repeated multiple times until the desired thickness was obtained (220 nm). After the dip coating process the glass coating films were treated at 100 °C for 10 min in an electric oven to evaporate the solvent and to remove organic residues followed by calcination of these films at 350 °C for 2 h.

The zinc hydroxide synthesis was carried out according to the following chemical equation:



Calcination at 350 °C for 2 h allowed transformation of zinc hydroxide to zinc oxide:



Copper doped zinc oxide thin films have been deposited on a glass substrate according to the above procedure with addition of the required amounts of copper nitrate to allow from 1 wt% to 5 wt% of copper. The required amount of copper nitrate was added to the zinc acetate solution, then left stirring until a clear homogeneous viscous solution formation. This viscous solution was served as the coating source.

The X-ray diffraction (XRD) of the films prepared was carried out with Rigaku-Ultima-IV X-ray diffractometer, Seron Inc. Transmission electron microscopy (TEM), selected area electron diffraction (SAED) and energy dispersive X-ray spectroscopy (EDS) were carried out with AIS 2100 TEM microscope at accelerating voltage of 200 kV. The optical measurements were conducted with WVASE32 ellipsometry supplied by J.A. Woollam Co., Inc. and the electrical measurements were performed with the Keithley 6514 electrometer.

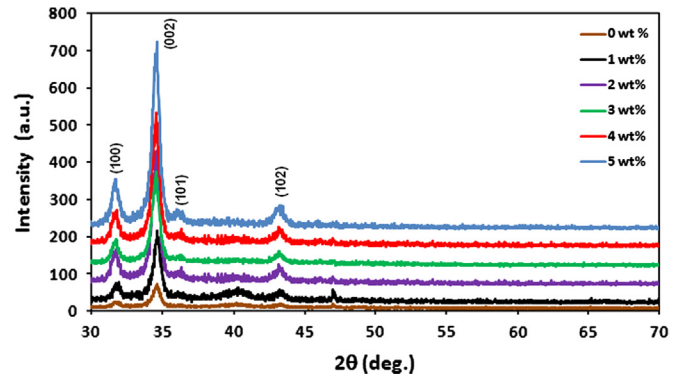


Fig. 1. XRD patterns for copper doped zinc oxide thin films.

## 3. Results and discussion

### 3.1. X-ray diffraction analysis of copper doped zinc oxide thin films

Fig. 1 depicts a typical X-ray diffraction patterns for the Cu-doped with ZnO thin films at different dopant concentrations. The diffraction peaks at the angles 31.4°, 34.53°, 36.5° and 43.2° are assigned to the reflections from the (100), (002), (101) and (102) planes, respectively. All the patterns are assigned to the hexagonal zinc oxide structure according to ASTM data card 5-664 [18]. No phase corresponding to copper or copper oxide was detected in the XRD patterns. According to the results obtained from XRD measurements one can conclude that the zinc oxide hexagonal structure is preserved up to 5 wt% of the copper dopant. The preferential orientation is along the (002) crystal plane at  $2\theta = 34.53^\circ$  for all prepared films. The diffraction peak (002) is also slightly shifted as the Cu-dopant concentration increased. This resulted in a change in the lattice constants. In order to calculate the lattice constant parameters, the Bond Model was utilized [19]. According to Bragg's law, the inter-space lattice parameter,  $d_{hkl}$ , can be estimated from the diffraction angle as follows

$$\lambda = 2d_{hkl} \sin \theta \quad (1)$$

where  $\lambda$  is the wavelength of the X-ray source and  $d_{hkl}$  is the lattice spacing parameter.

Eq. (1) may be written in the form

$$\frac{1}{d_{hkl}^2} = \frac{4}{\lambda^2} \sin^2 \theta \quad (2)$$

For hexagonal crystal structure, the lattice constants,  $a$  and  $c$ , may be given as

$$\frac{1}{d_{hkl}^2} = \frac{4(h^2 + hk + k^2)}{3a^2} + \frac{l^2}{c^2} \quad (3)$$

Combining (2) with (3), one obtains

$$\sin^2 \theta = \left[ \frac{\lambda^2}{3a^2} (h^2 + hk + k^2) \right] + \left[ \frac{\lambda^2}{4c^2} l^2 \right] \quad (4)$$

The  $a$  and  $c$  lattice constants for the copper doped zinc oxide hexagonal structure was estimated according to Eq. (4) and presented in Fig. 2.

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